

## Venue

The Conference will be held in the Hotel “Holiday Inn St.Petersburg” located on a straight way from Pulkovo Airport (25 min) to St. Petersburg downtown (15 min).

Hotel «Holiday Inn St. Petersburg» offers:

- Congress hall for 450 people, provided with necessary modern equipment
- Spacious foyers around the hall for poster sessions, coffee-breaks, and exhibition
- Several restaurants to organize welcome reception and lunches for 250 persons simultaneously
- Wi-Fi Internet connection for the symposium participants in public places



## Accommodation

Hotel «Holiday Inn St.Petersburg» will provide ~50 comfortable rooms with a conference discount (rates 110-120 EUR per night) for Workshop participants.

Participants who would like to stay in the hotel “Holiday Inn St. Petersburg” are to complete an Accommodation Form, which will be available on June 1, 2019, at the Workshop website. The Accommodation Forms will be collected and processed by the Organizing Committee with the preference to early booking.

Participants can also book different hotels in the very downtown for 50-100 EUR per night. It takes 15 min max by subway to get to the Workshop venue.



Please send correspondence to the Secretary  
Dr. Tatiana Komissarova, Ioffe Institute  
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Fax: +7 (812) 297-1017, Phone: +7 (812) 292-7124  
e-mail: iwumd4@mail.ioffe.ru & iwumd4@gmail.ru

## Registration fee

	Early registration, EUR, before 30.06.2019	Late registration, EUR, after 30.06.2019
Regular participants	550	650
Student participants	350	400
Accompanying persons	270	350

Registration Fee covers admission to all Workshop sessions, a Workshop program and abstracts booklet, Welcome party (Monday, September 9), Workshop dinner (Thursday, September 12), coffee breaks, lunches, poster refreshments, sightseeing tour (Thursday, September 12), and visa support.

Registration Fee for accompanying persons covers Welcome party, lunches, Workshop dinner, coffee breaks, sightseeing tour, and visa support.

## Exhibition

Exhibition of products and services related to UV materials, devices, and technologies will be held as an integral part of the Workshop. The detailed information on exhibitor's registration and conditions is available at the Workshop website.

## Visa support

Participants who need a visa to enter Russian Federation are to complete the relevant fields in the Visa Form, which will be available from June 1, 2019, and send it with a scanned copy of the passport page with a photo to Organizing Committee by e-mail. After submission of the Visa Form the official Invitation letter from Ioffe Institute or from the Ministry of Foreign Affairs depending on the participant citizenship will be sent to the participants for application for the Russian humanitarian visa.

## Important dates

Abstract submission  
deadline (extended)

May 20, 2019

Notification of abstract acceptance

June 10, 2019

Deadline for post-deadline  
abstract submission

June 30, 2019

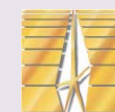
[www.ioffe.ru/IWUMD4](http://www.ioffe.ru/IWUMD4)

# 4th International Workshop on Ultraviolet Materials and Devices



September 8-13, 2019,  
Saint Petersburg, Russia

Workshop Chair  
Sergey Ivanov, Ioffe Institute, Russia



Ioffe  
Institute



Second announcement  
Call for abstracts

[www.ioffe.ru/IWUMD4](http://www.ioffe.ru/IWUMD4)

The 4th International Workshop on Ultraviolet (UV) Materials and Devices (IWUMD4) is organized by Ioffe Institute (St. Petersburg, Russia) and continues a series of the successful meetings of UV community, held in Beijing, China (2016), Fukuoka, Japan (2017), Kunming, China (2018). The workshop gets together prominent and young scientists in warm and friendly atmosphere. It provides a unique opportunity for the presentation and open discussion of latest results on R&D of novel UV materials and devices, new trends in basic and applied studies, modelling, and innovative technologies.

### Main scientific topics:

- AlN bulk crystals and templates
- Growth and properties of AlGaIn heterostructures
- BN growth and fundamental properties
- Oxides (Ga<sub>2</sub>O<sub>3</sub>, etc.) growth and fundamental properties
- Wide-gap heterostructure physics
- Nanostructures and nanodevices
- UV photonic AlGaIn devices
- Non-AlGaIn UV photonic devices

### Advisory committee

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**Y. Kawakami** (Kyoto University, Japan)  
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**B. Shen** (Peking University, China)  
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**S.Yu. Karpov** (STR Group, Russia)  
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**E. Monroy** (CEA-Grenoble, France)  
**S.-J. Park** (GIST, Korea)  
**P. Perlin** (UNIPRESS, Poland)  
**L. Schowalter** (Crystal-IS, USA)  
**X. Q. Wang** (Peking University, China)  
**J. Wang** (Institute of Semiconductors, CAS, China)  
**T. Wang** (University of Sheffield, UK)  
**C. Wetzel** (Rensselaer, USA)  
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### Organizing committee

at Ioffe Institute

**Sergey Ivanov** - Chair

**Tatiana Komissarova** - Secretary

**Irina Sedova, Anton Lebedev,**

**E. Moltchanova, J. Senchenok**

### Abstract submission

Abstract Deadline (extended) is **May 20, 2019**.

For details please visit the website:

<http://www.ioffe.ru/IWUMD4>

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[iwumd4@gmail.com](mailto:iwumd4@gmail.com)**

### Plenary Speakers

**Michael Kneissl**, TU Berlin, Germany

**Chris Van de Walle**, UCSB, USA

### Keynote Speakers

**Guillaume Cassabois**, Montpellier University, France

**Hideki Hirayama**, RIKEN, Japan

**James Speck**, UCSB, USA

**Alexey Toropov**, Ioffe Institute, Russia

### Invited Speakers

**Masayoshi Adachi**, Tohoku University, Japan

**Shigefusa Chichibu**, Tohoku University, Japan

**Juergen Christen**, Magdeburg University, Germany

**Bruno Daudin**, CEA-Granoble, France

**Sven Einfeldt**, Ferdinand-Braun-Institut, Germany

**Giorgia Fugallo**, Universite Paris-Saclay, France

**Akira Hirano**, UV Craftory Co. Nagoya, Japan

**Axel Hoffmann**, TU Berlin, Germany

**Shin-ichiro Inoue**, Advanced ICT Research Inst., Japan

**Motoaki Iwaya**, Meijo University, Japan

**Debdeep Jena**, Cornell University, USA

**Emmanouil Kioupakis**, University of Michigan, USA

**Liverios Lymperakis**, MPIE, Germany

**Hideto Miyake**, Mie University, Japan

**Sergei Novikov**, University of Nottingham, UK

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**Markus Wagner**, TU Berlin, Germany

**Junxi Wang**, Institute of semiconductors, China

**Xinqiang Wang**, Peking University, China

**Kenji Watanabe**, NIMS, Japan

**Markus Weyers**, Ferdinand Braun Institute, Germany

**Grace Xing**, Cornell University, USA

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